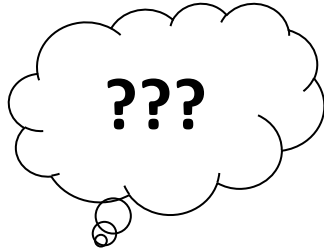


INTEGRATED PHOTONIC MODULATORS BASED ON GRAPHENE AND OTHER 2D MATERIALS FOR OPTICAL INTERCONNECTS

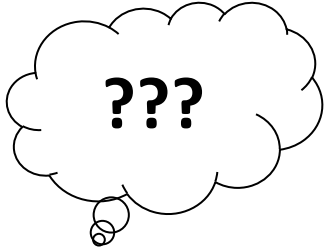
Chenghan (Kenny) Wu

WHAT IS...?



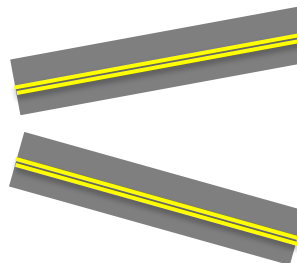
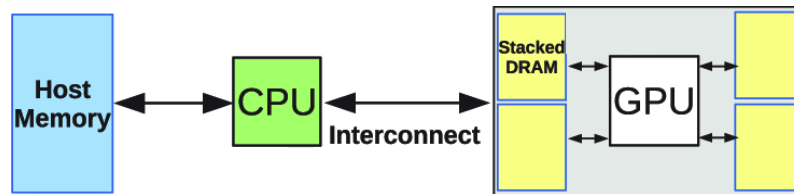
Integrated Photonic Modulators Based
on Graphene and Other 2D Materials
for Optical Interconnects

WHAT IS...?



Integrated Photonic Modulators Based on Graphene and Other 2D Materials
for Optical Interconnects

INTERCONNECT

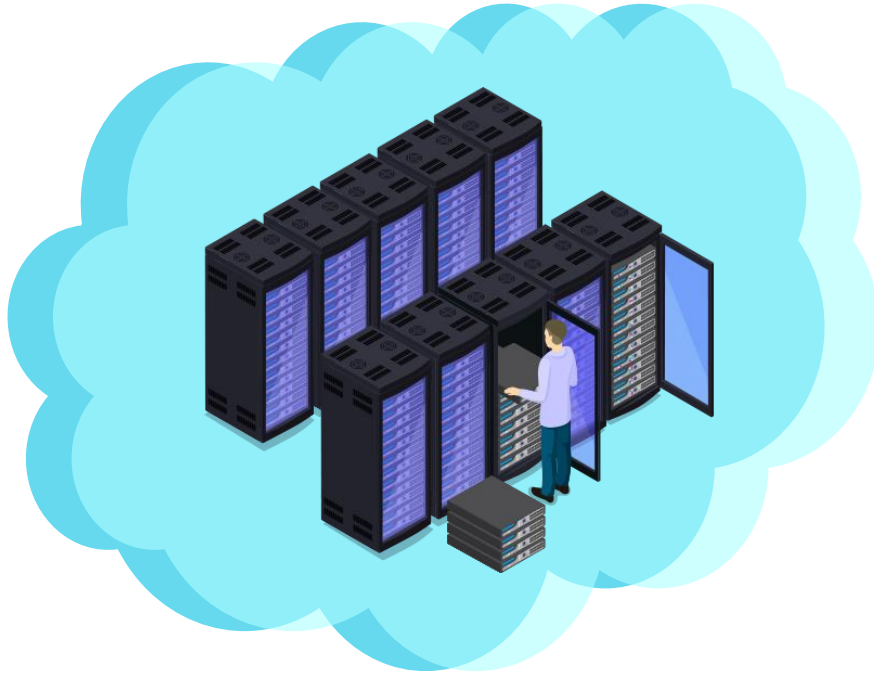


INTERCONNECT NETWORK

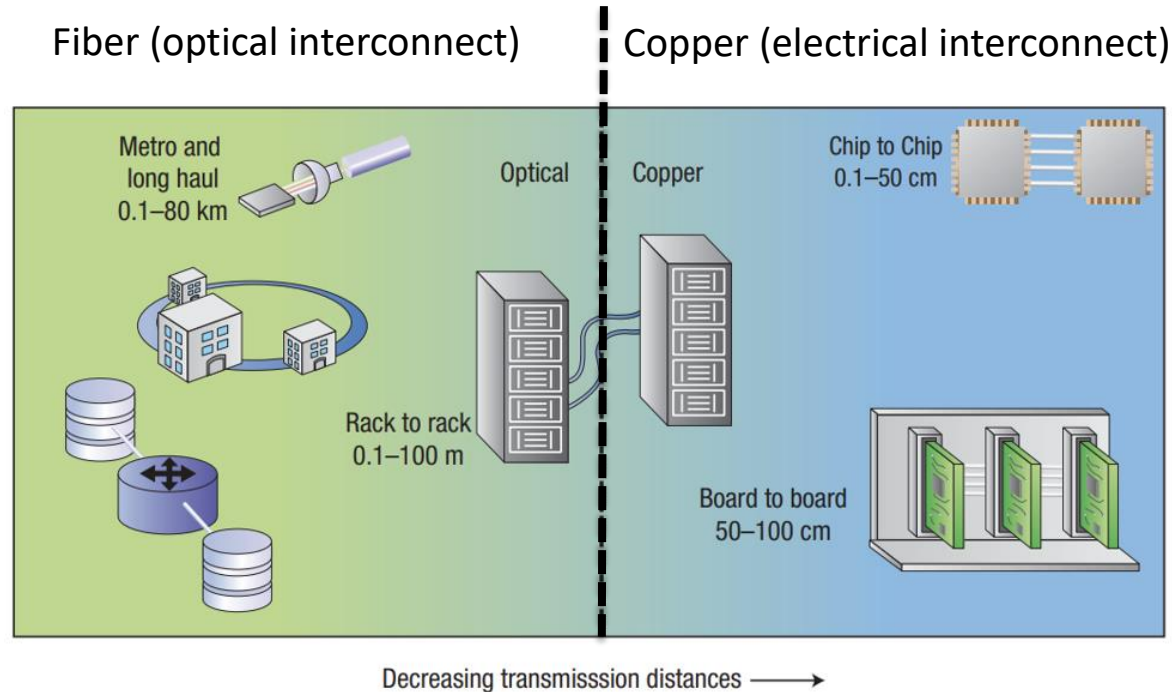


This interconnected network enables seamless communication and access to various online services.

DATA CENTER

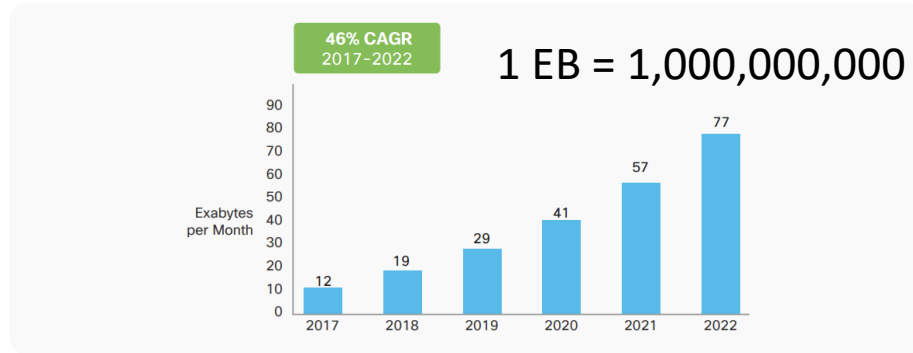


COMMUNICATION LEVEL

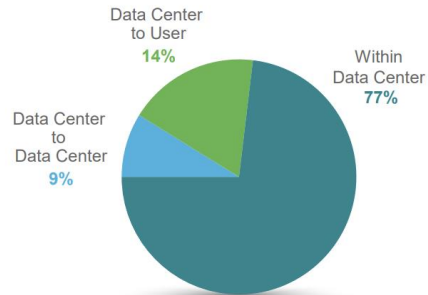


INCREASED DATA TRAFFIC

Figure 2. Cisco Forecasts 77 Exabytes per Month of Mobile Data Traffic by 2022



Source: Cisco VNI Mobile, 2019



Total East-West Traffic Is 86%
 (Rack-local traffic would add another slice twice the size of "Within Data Center")



A Within Data Center (77%)



Storage, production and development data, authentication

B Data Center to Data Center (9%)



Replication, CDN, intercloud links

C Data Center to User (14%)

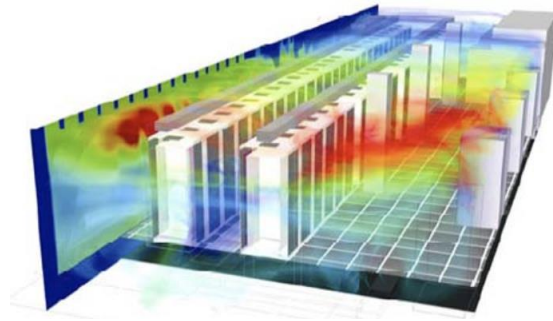


Web, email, internal VoD, WebEX...

[Back to Index](#)

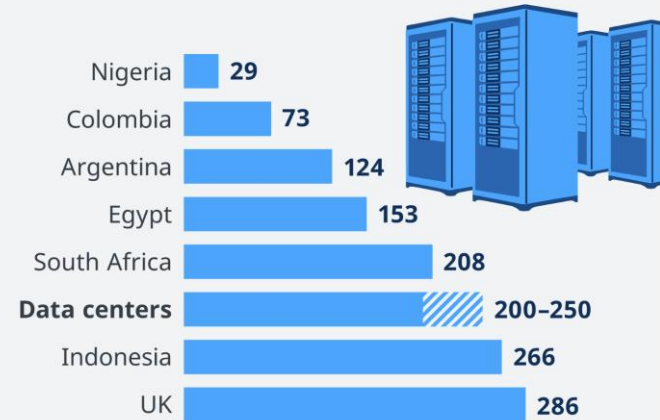
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CHALLENGES FOR DATA CENTER



Data centers use more electricity than entire countries









Domestic electricity consumption of selected countries vs. data centers in 2020 in TWh



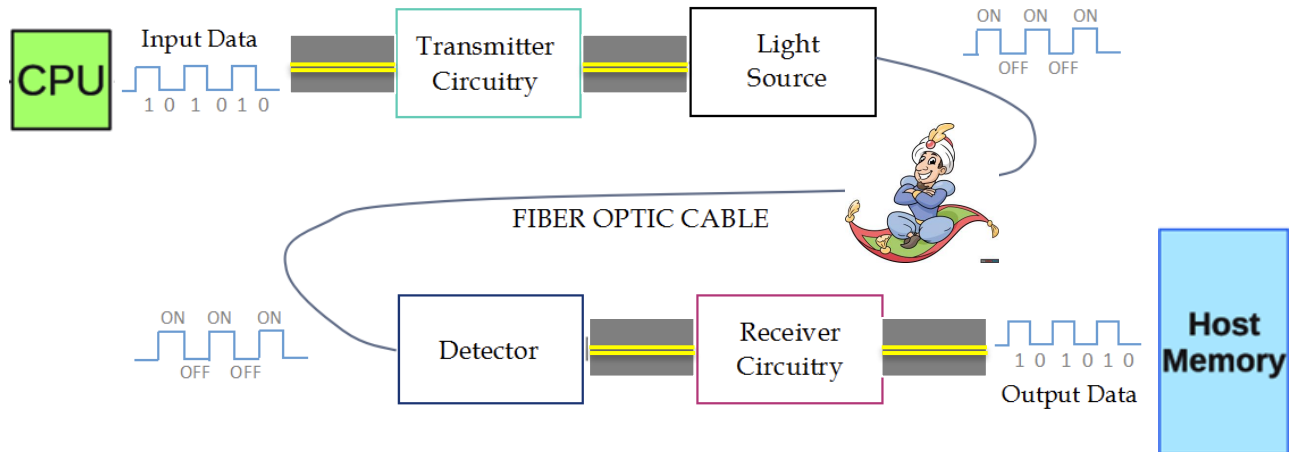
Source: Enerdata, IEA

ELECTRICAL AND OPTICAL INTERCONNECT

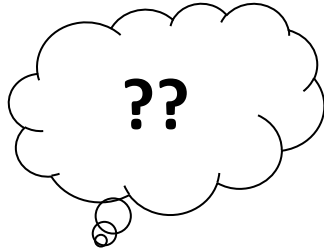


	Electrical interconnect	Optical interconnect
Bandwidth / data rates		
Power consumption		
Cost		
Compatibility with existing data center		

OPTICAL INTERCONNECT



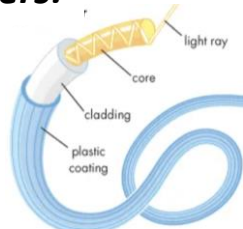
WHAT IS...?



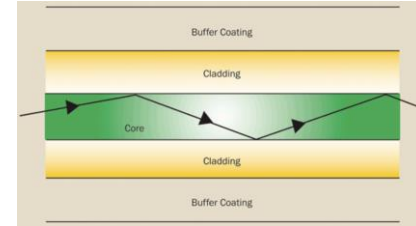
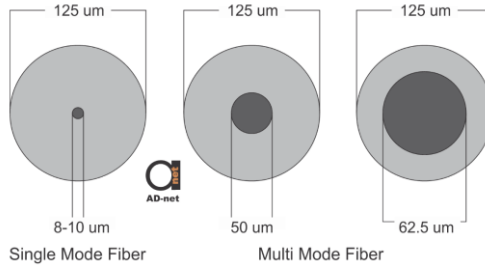
Integrated Photonic Modulators Based
on Graphene and Other 2D Materials
for Optical Interconnects

SILICON WAVEGUIDES = FIBERS IN CHIP

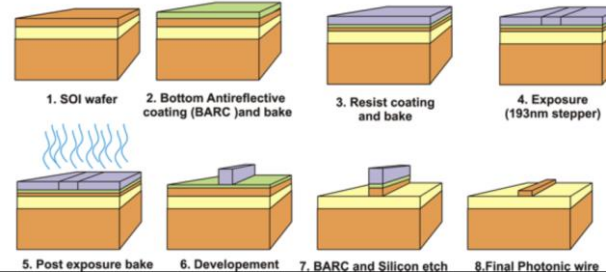
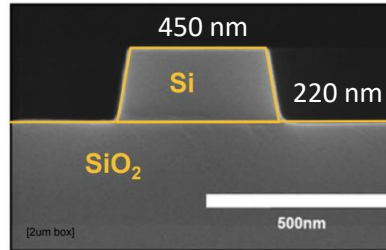
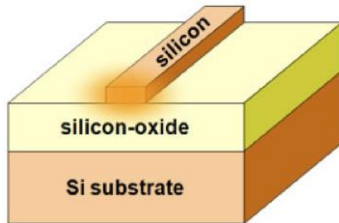
Fibers:



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Waveguides:



INTEGRATED SILICON PHOTONICS

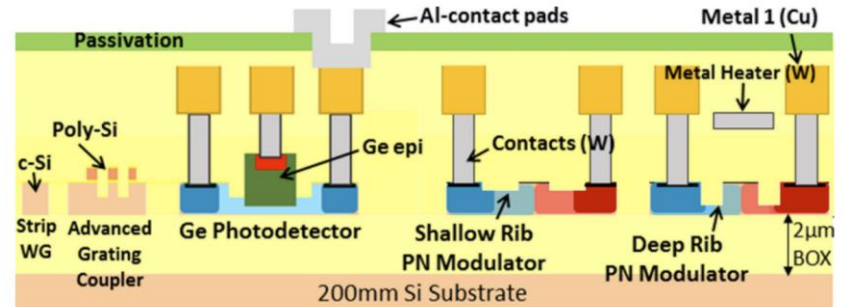
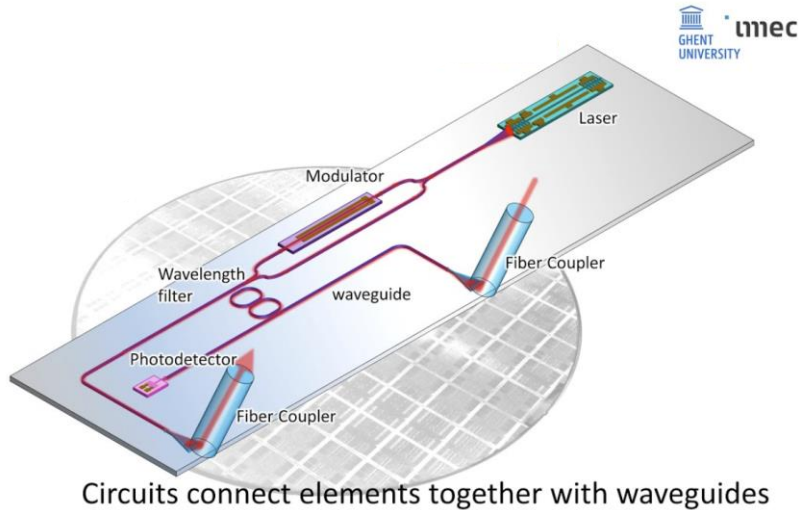
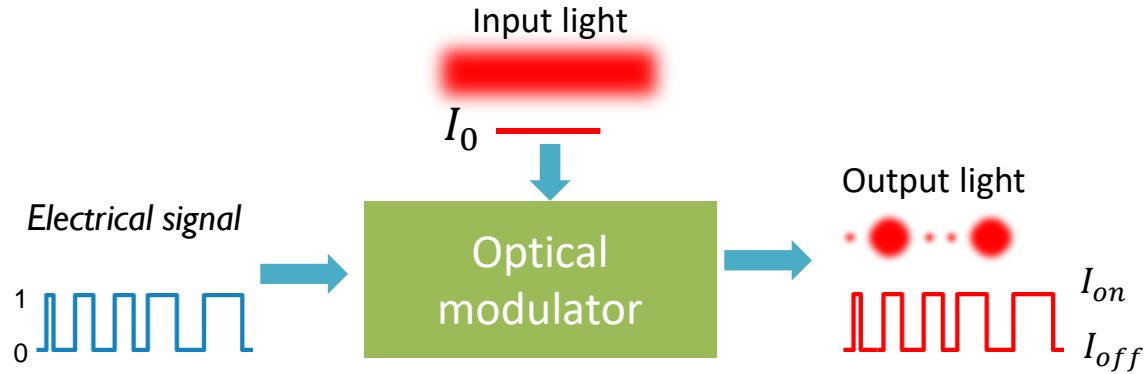


Figure 1.2: Schematic cross-section of imec's silicon photonics platform, with the basic passive and active devices. Taken from [2].

MODULATOR



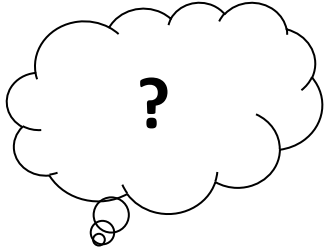
Amplitude modulation (AM)



Phase modulation (PM)



WHAT IS...?

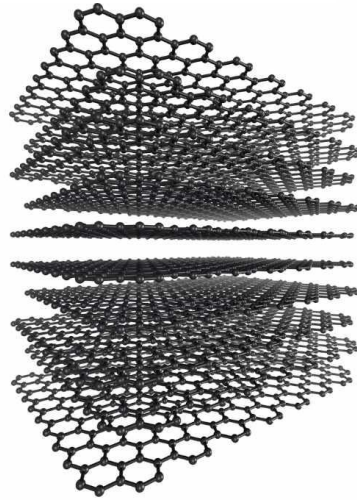


Integrated Photonic Modulators Based
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for Optical Interconnects

THE FIRST 2D MATERIAL : GRAPHENE



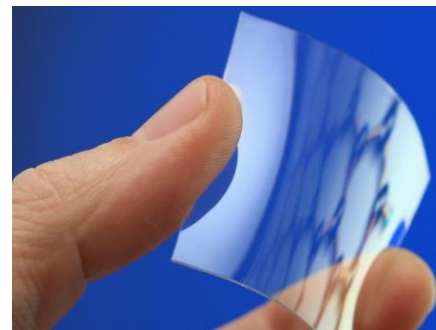
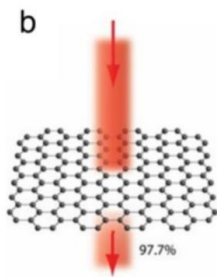
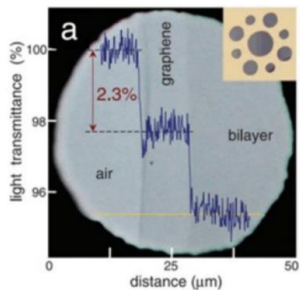
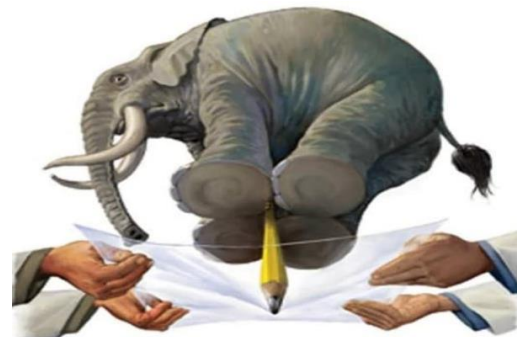
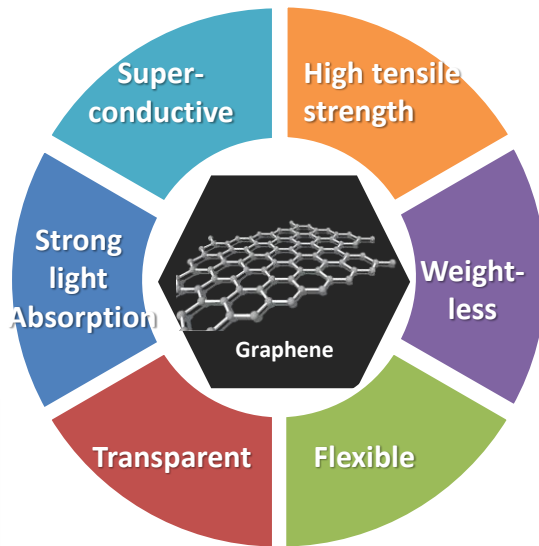
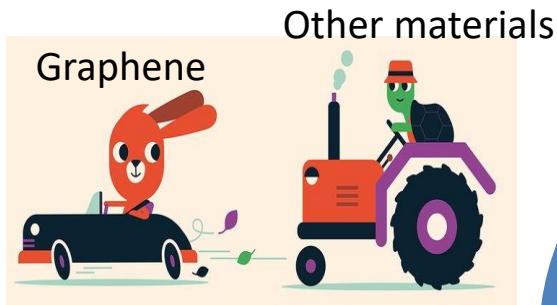
Graphite



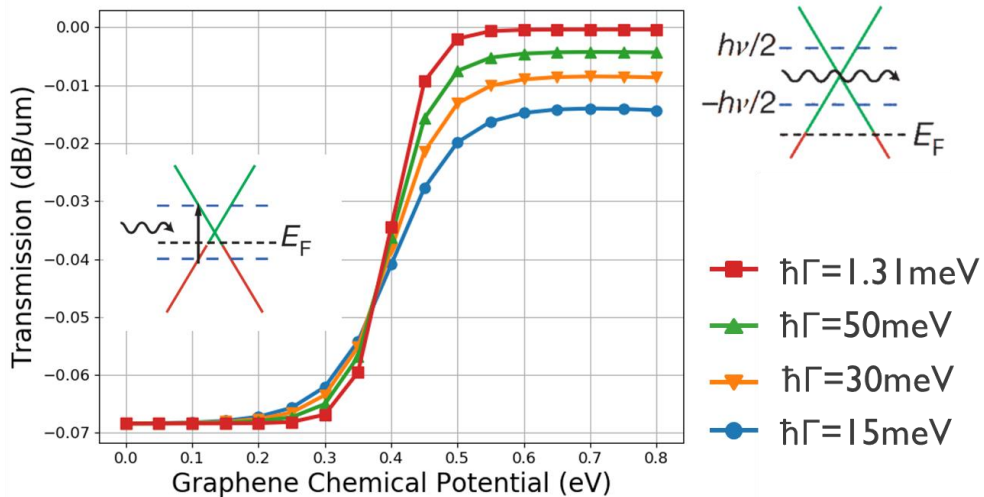
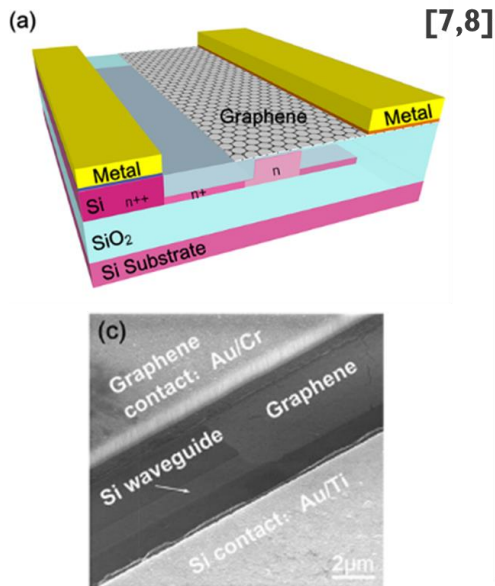
Graphene →



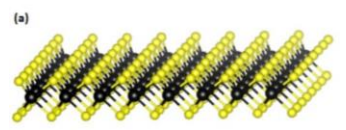
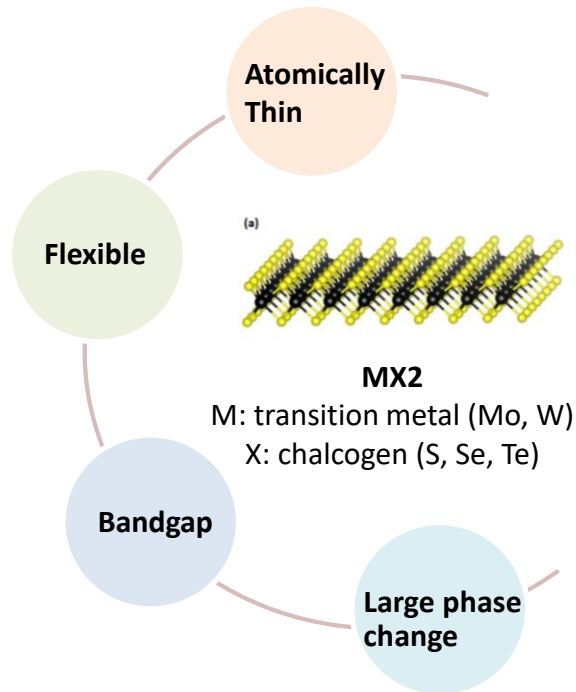
GRAPHENE: SUPER HERO IN MATERIALS



GRAPHENE + INTEGRATED PHOTONICS MODULATORS

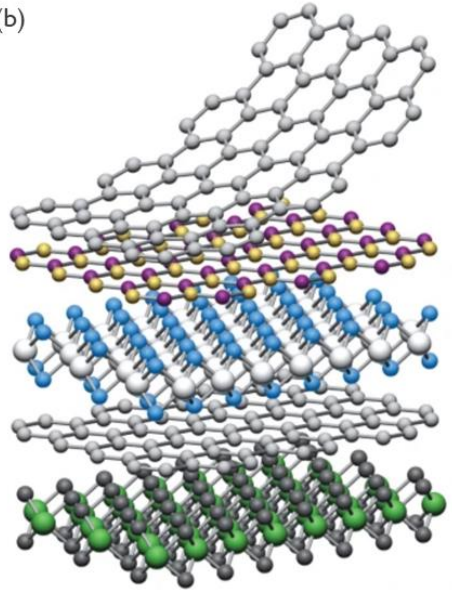


OTHER 2D MATERIALS

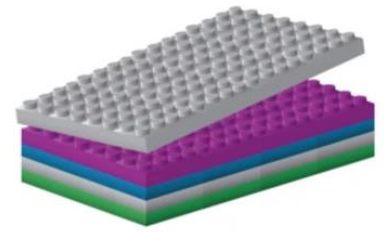


MX₂
 M: transition metal (Mo, W)
 X: chalcogen (S, Se, Te)

(b)



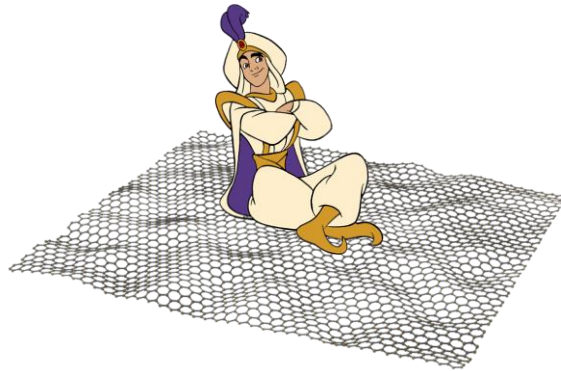
	Graphene	
	hBN	
	MoS ₂	
	WSe ₂	
	Fluorographene	



WHAT IS...?



Integrated Photonic Modulators Based on Graphene and Other 2D Materials for Optical Interconnects



RESEARCH OBJECTIVES

Can 2D material based photonic devices be adopted in industry for the next generation of data communication and telecommunications applications?

SCALABILITY



- Establishment of inline integration
- 3 optimization directions

PERFORMANCE



- Electro-absorption Modulators
- Mach-Zehnder Modulators
- Ring Modulators

EXPLORATORY



- Doped-Si/Oxide/MoS₂
- Graphene/Oxide/MoS₂
- MoS₂/Oxide/MoS₂

SCALABILITY!

WAFER-SCALE INTEGRATION OF
GRAPHENE EAM IN 300 MM CMOS
PILOT LINE

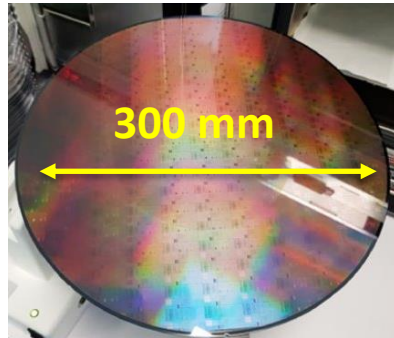
MOTIVATION

Most research studies on **small coupons without CMOS-compatible technology**, which are not compatible with high-volume industrial manufacturing.

Small coupons
2x1 cm²



Develop robust inline integration flow in a 300mm pilot CMOS foundry environment.



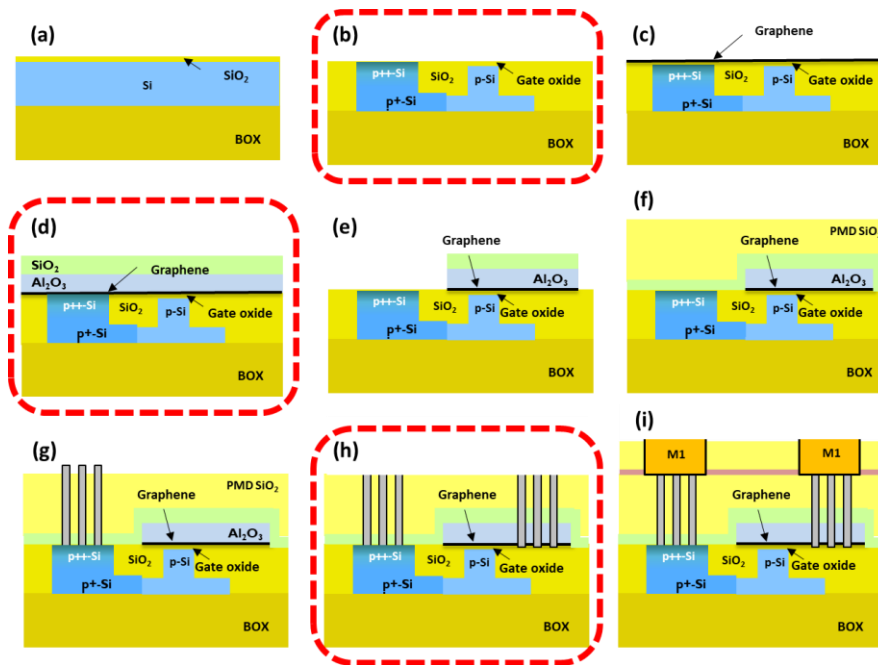
300 mm wafer
(>50 dies)



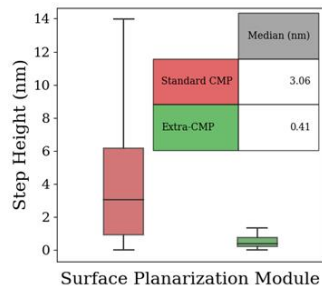
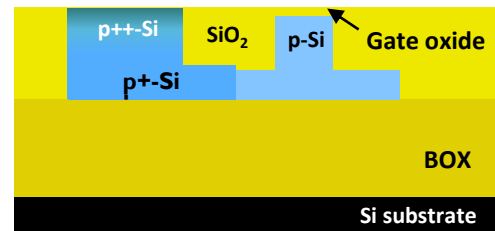
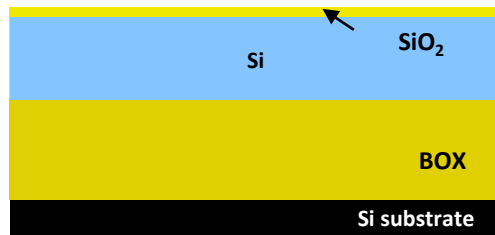
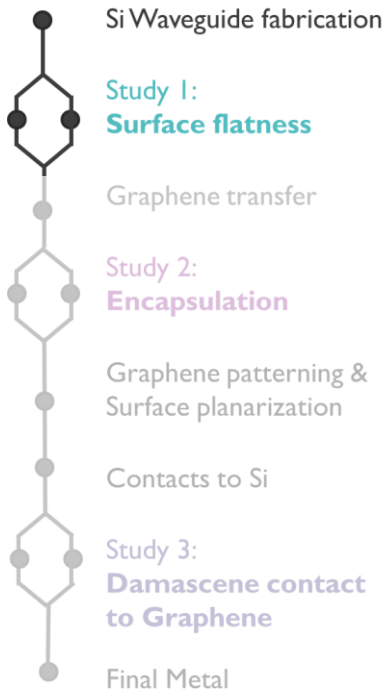
CHALLENGES AND STRATEGY

The challenges:

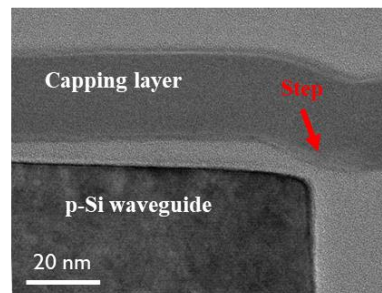
1. Developing CMOS-compatible processes for lithography and contact.
2. Scaling up graphene growth and transfer methods for large-scale production.
3. Designing an efficient capping layer to safeguard graphene from delamination.
4. Minimizing contact resistance to enable high-speed performance in graphene-based devices.



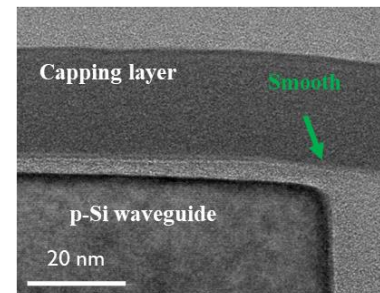
PHASE 1 STUDY: FAB-LEVEL INTEGRATION FLOW



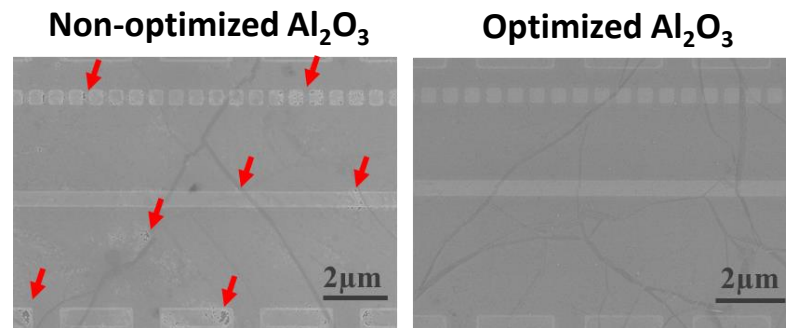
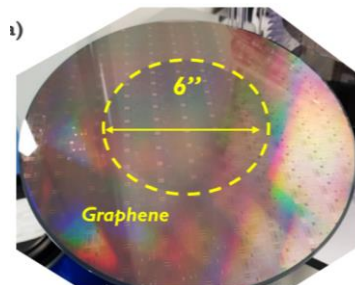
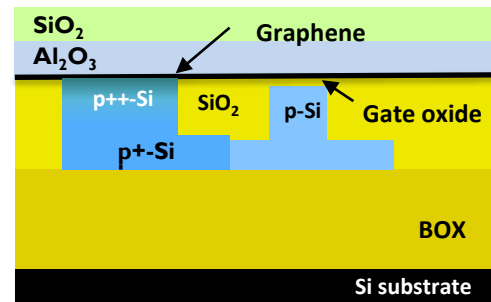
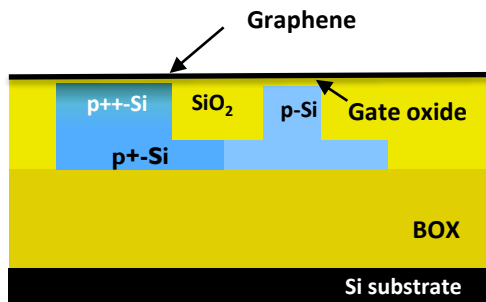
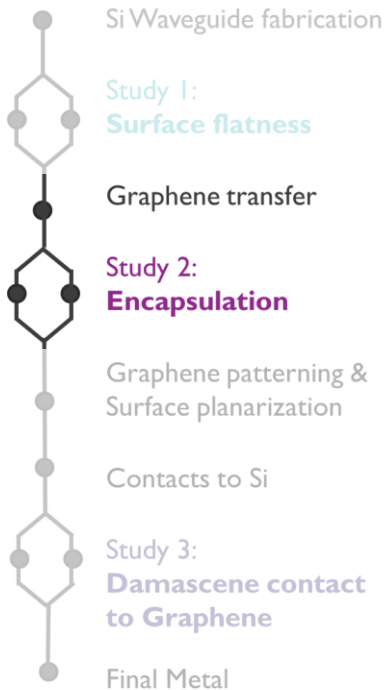
Standard CMP



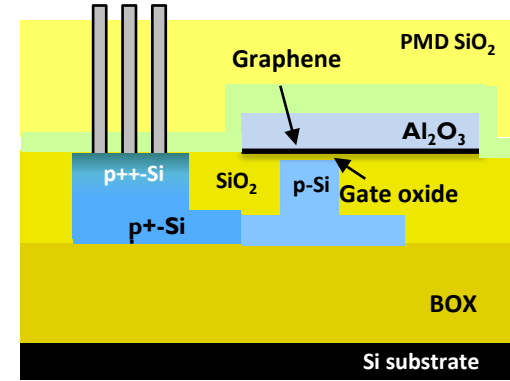
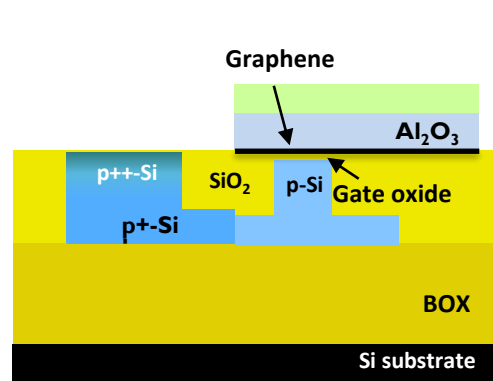
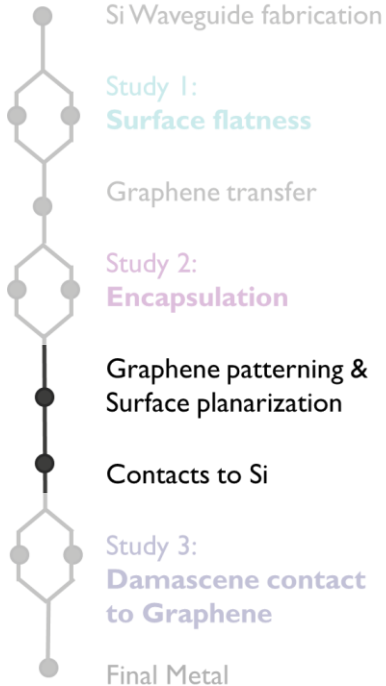
Extra CMP



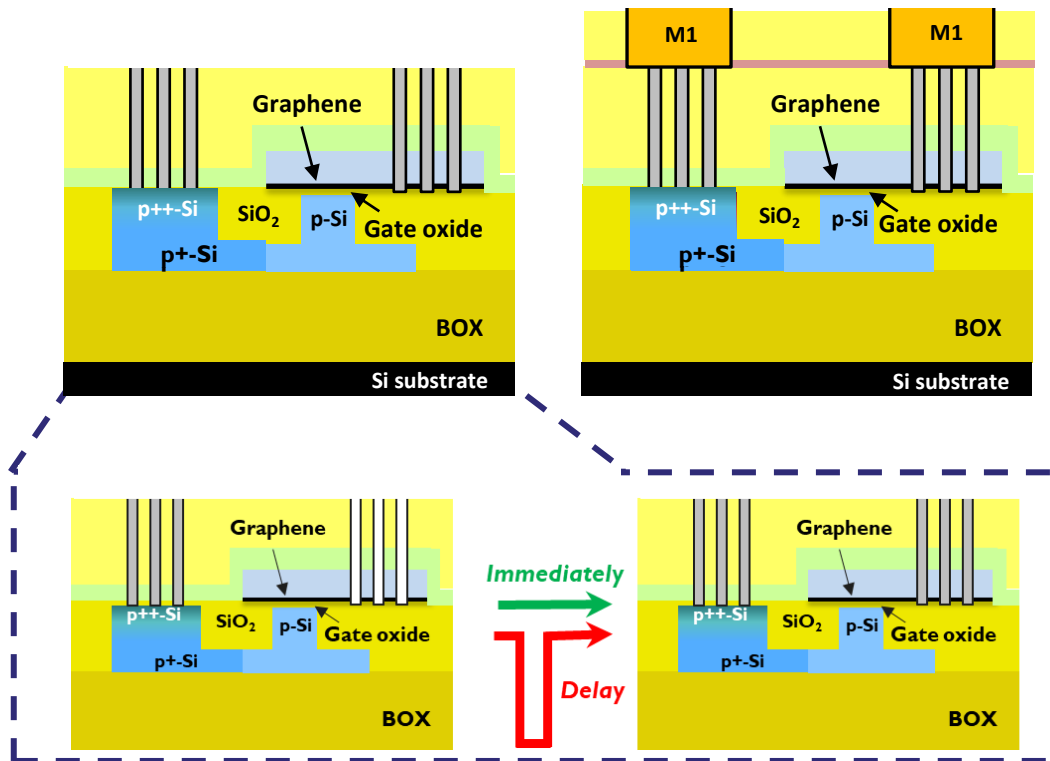
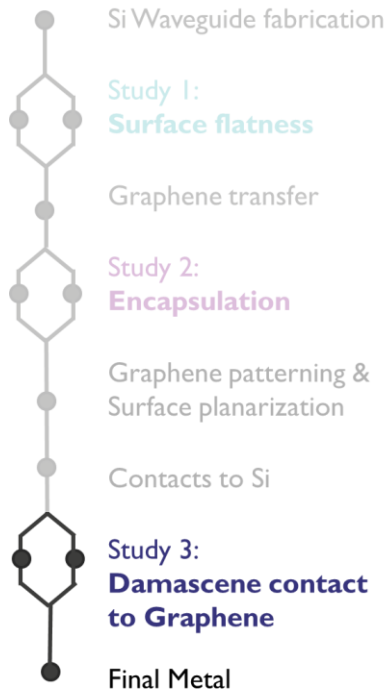
PHASE 1 STUDY: FAB-LEVEL INTEGRATION FLOW



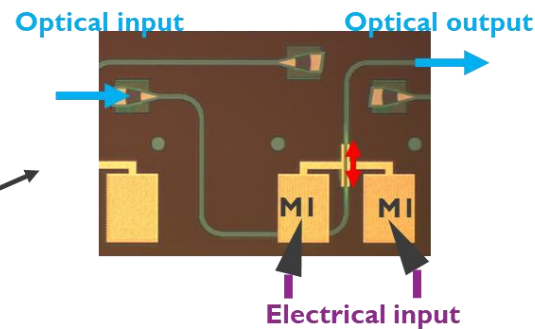
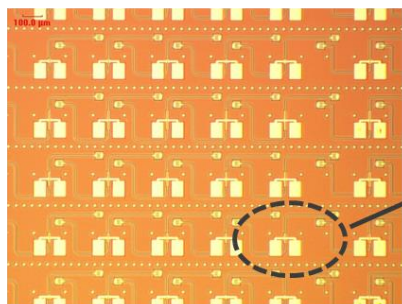
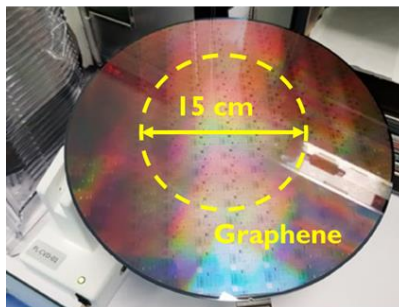
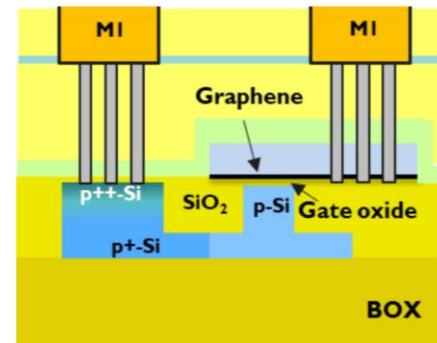
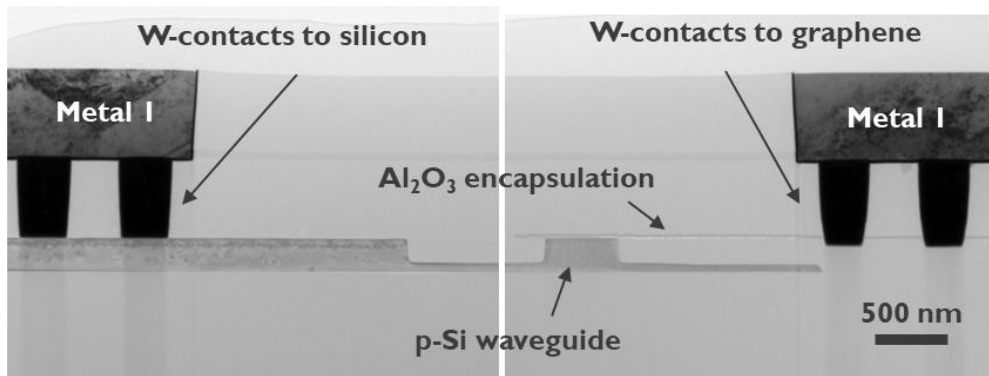
PHASE 1 STUDY: FAB-LEVEL INTEGRATION FLOW



PHASE 1 STUDY: FAB-LEVEL INTEGRATION FLOW



DEVICES' LOOK



CHARACTERIZATION

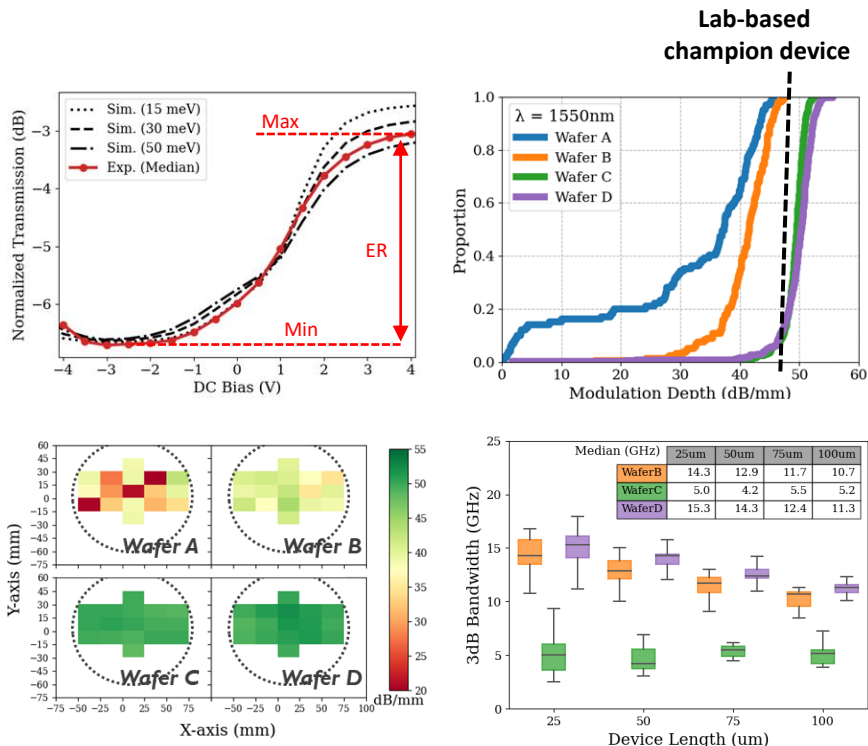


Table 1: DOE summary of four wafers reported in this paper

DOE	Wafer A	Wafer B	Wafer C	Wafer D
Surface planarization	Standard STI	Standard STI	Extra CMP	Extra CMP
Encapsulation soaking	Short	Long	Long	Long
Contact metal deposition	No delay	No delay	2 days delay	No delay

Study 1 on surface planarization: (Wafer B vs Wafer D)

Devices with Extra CMP modules results in a better modulation depth.

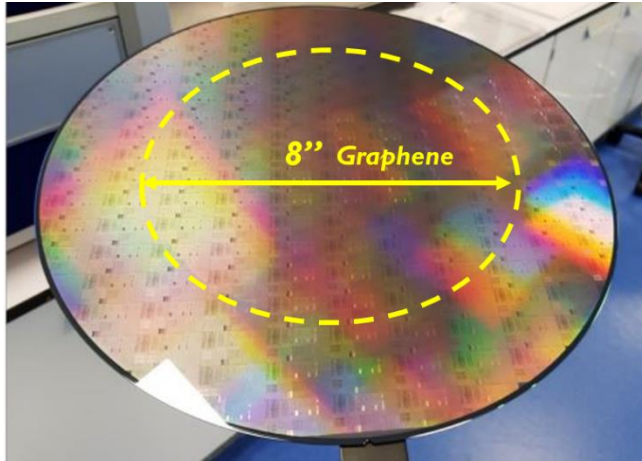
Study 2 on encapsulation soaking: (Wafer A vs Wafer B)

Devices with longer soaking results in a better device yield.

Study 3 on contact metal: (Wafer C vs Wafer D)

No difference is observed in static characterization. In dynamic characterization, Devices with no-delay contacts results in larger bandwidth.

WRAP-UP



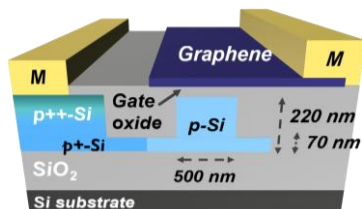
Graphene photonics devices are now fully integrated with CMOS technology on 300 mm wafers!

Technology		Wafer-scale SLGEAM - Wafer D		Lab-based Champion SLGEAM	
		This work		[1]	
Active length	um	50	75	75	75
Working band & mode	-	C-band TE		C-band TE	
Oxide stack(s)	-	SiO2		SiO2	
Peak-to-peak Voltage	V	5		~5	
IL @highV	dB	2.0 ± 0.7	3.5 ± 1.5	~2.5	3
ER	dB	2.5 ± 0.1	3.7 ± 0.3	3.6	2.7
Modulation depth	dB/mm	50 ± 4.0		48	36
FOM(ER/IL)	-	1.28 ± 0.23	1.30 ± 0.31	1.52	0.87
Transmission Penalty	dB	7.39 ± 0.76 Best device: 6.44	7.90 ± 1.70 Best device: 6.76	8	9.4
3dB bandwidth	GHz	14.1 ± 1.4	12.6 ± 0.9	8.9	16.1
Number of devices	-	> 400		1	1

PERFORMANCE!

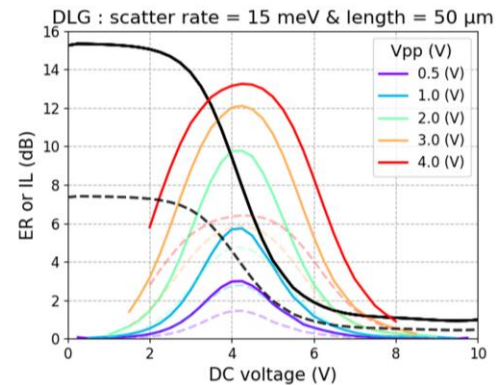
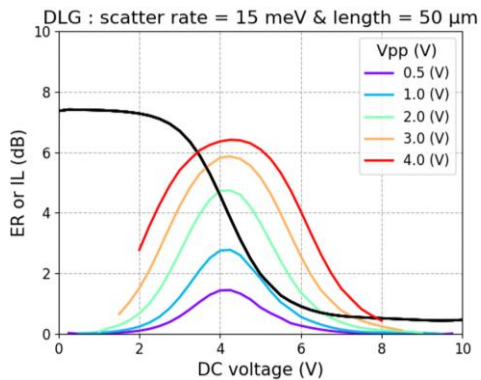
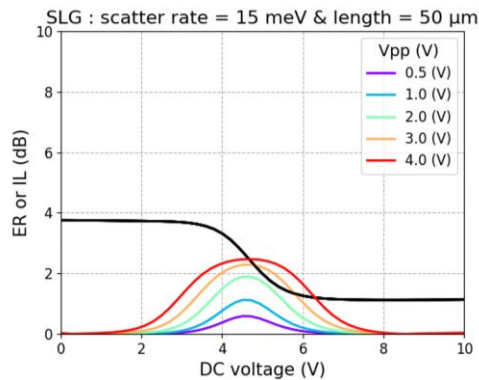
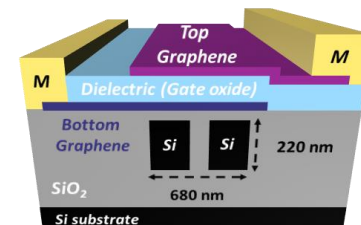
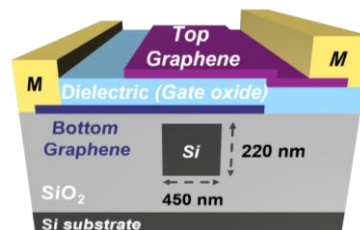
HIGH-EFFICIENCY DUAL SINGLE LAYER
GRAPHENE MODULATORS WITH STRIP
AND SLOT WAVEGUIDES

MOTIVATION



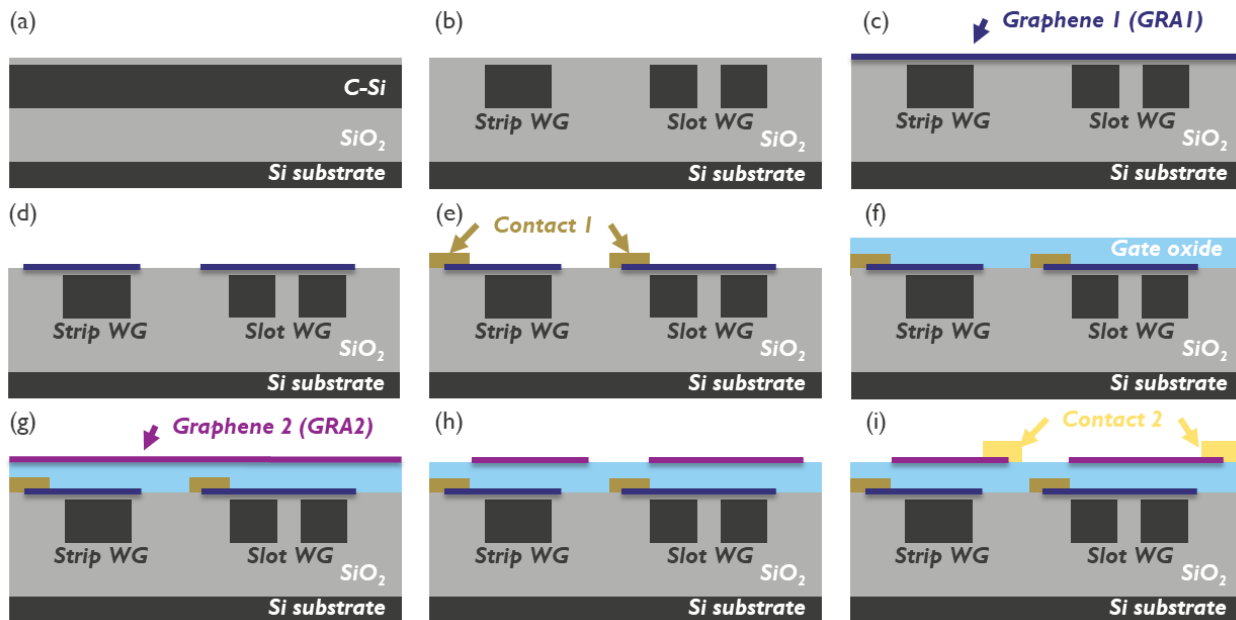
*Increase modulation
No need Si implantation
Any passive WG*

More complicated integration

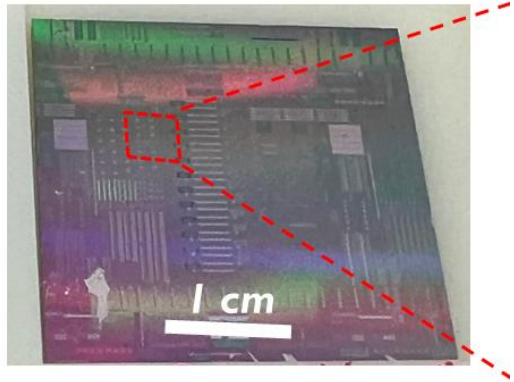


--- Strip waveguide-based
— Slot waveguide-based

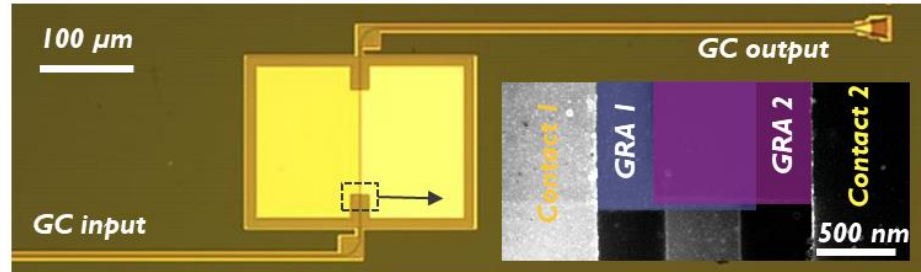
LAB-LEVEL INTEGRATION FLOW



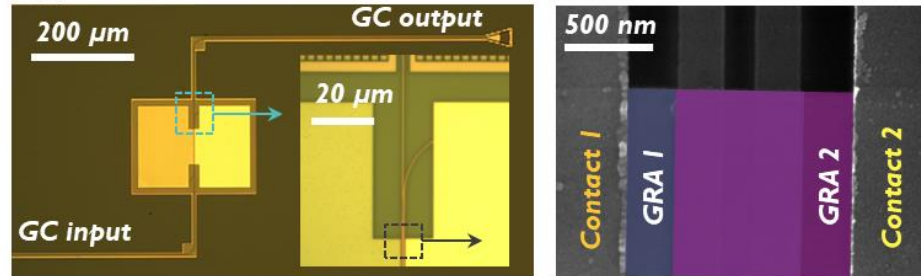
DLG EAMs



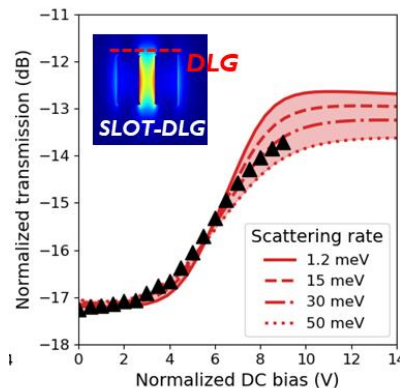
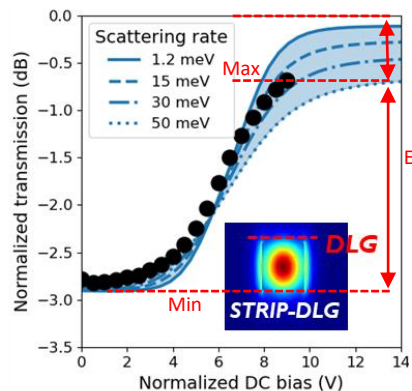
(a)



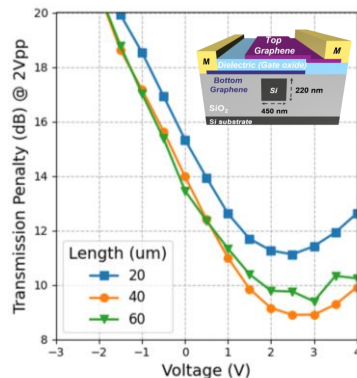
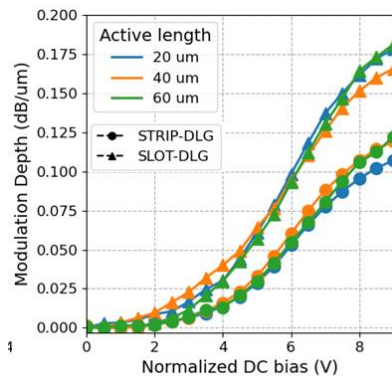
(b)



DLG EAMs DC PERFORMANCE

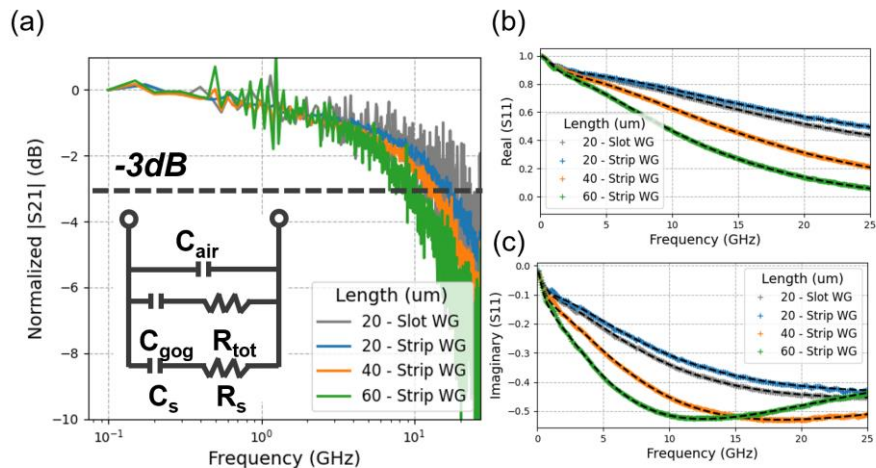


$$\begin{aligned} \text{Transmission Penalty [dB]} \\ = \frac{P_1 - P_0}{2P_{in}} = -10 \log_{10}\left(\frac{1 - \frac{1}{ER}}{2 IL}\right) \end{aligned}$$

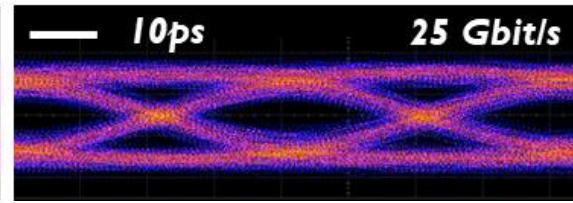
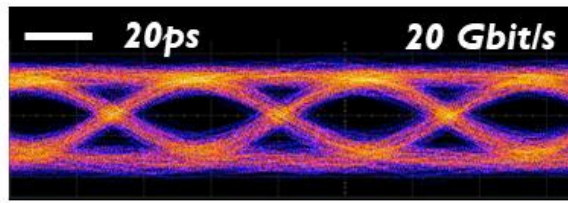
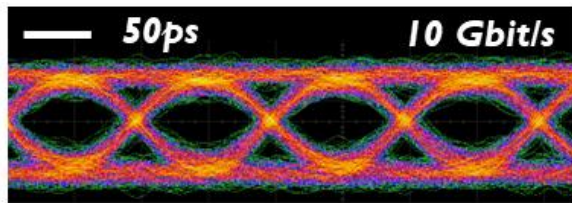


- **Strip:** MD = 0.125 dB/um; TP = 8.9 dB @ 2 V_{pp}
- **Slot:** MD = 180 dB/um; TP > 20 dB @ 2 V_{pp}
- TP = 8.9 dB is best reported for graphene-based modulator and comparable with Ge device.

DLG EAMs AC PERFORMANCE



WG Type	Length	$f_{3\text{dB}}$	C_{gog}	R_{tot}
	[μm]	[GHz]	[fF]	[Ω]
Strip WG	20	15.9	45	116
	40	12.5	92	47
	60	9.2	139	43
Slot WG	20	15.9	53	101



DLG EAMs BENCHMARKING TABLE

Graphene-based EAMs		DLGEAM Strip WG	DLGEAM Slot WG	High-speed DLG-EAM [1]		High-speed DLG-EAM [2]
Peak-to-peak Voltage	V	7		12	16	~9
IL @highV	dB	0.88	14.4	20	14.3	~20
Modulation efficiency	dB/V/um	0.0213	0.039	0.0367	0.0295	-
Modulation depth	dB/mm	117	168	75	128	25
Transmission Penalty	dB	5.69	>20	25	18	26
3dB bandwidth	GHz	12.5	15.9	39	-	29

[1] Agarwal, Hitesh, et al. "2D-3D integration of hexagonal boron nitride and a high-κ dielectric for ultrafast graphene-based electro-absorption modulators." Nature communications 12.1 (2021): 1-6.

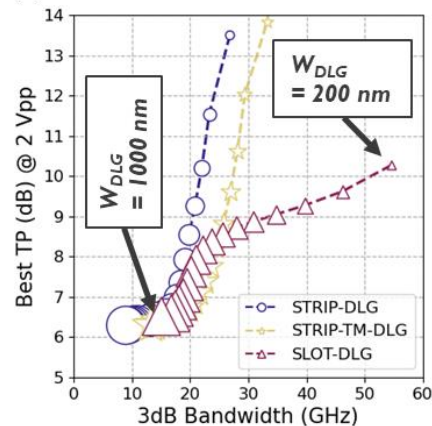
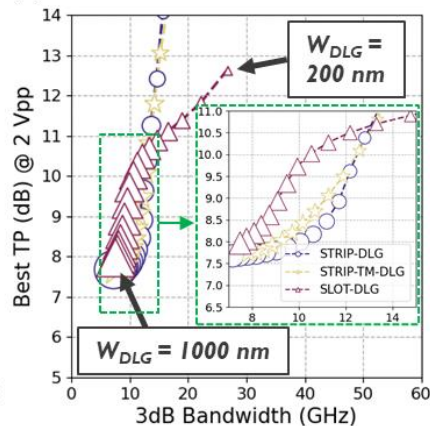
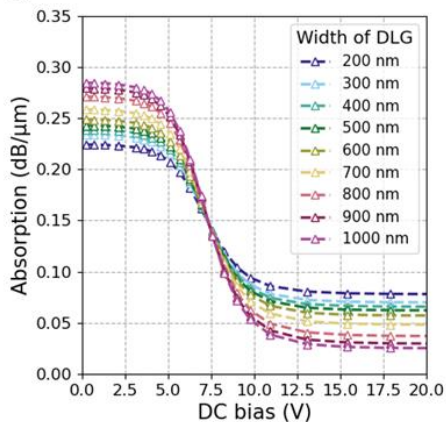
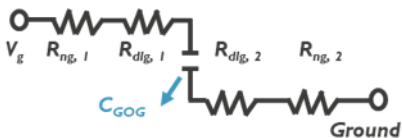
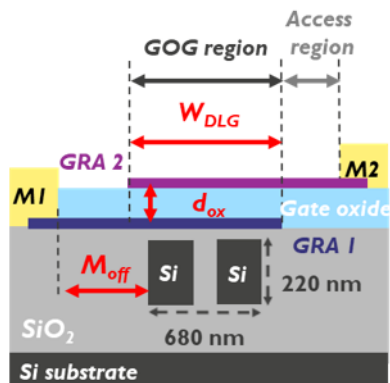
[2] Giambra, Marco A., et al. "High-speed double layer graphene electro-absorption modulator on SOI waveguide." Optics express 27.15 (2019): 20145-20155.

[3] Srinivasan, Srinivasan Ashwyn, et al. "56 Gb/s germanium waveguide electro-absorption modulator." Journal of Lightwave Technology 34.2 (2015): 419-424.

[4] Tang, Yongbo, Jonathan D. Peters, and John E. Bowers. "Over 67 GHz bandwidth hybrid silicon electroabsorption modulator with asymmetric segmented electrode for 1.3 μm transmission." Optics Express 20.10 (2012): 11529-11535.

EAMs with different materials		DLGEAM Strip WG	DLGEAM Slot WG	Ge FK EAM [3]	III-V EAM [4]
Peak-to-peak Voltage	V	2		2	2.2
IL @highV	dB	1.71	15	4.9	4.8
Modulation depth	dB/mm	52.2	71.5	115	>100
Transmission Penalty	dB	8.90	>20	9.76	~8.26
3dB bandwidth	GHz	12.5	15.9	>50	>67
Optical bandwidth	nm	>80 Expected		~30	>30
Temperature Tolerance	°C	>100 Expected		<30	-

ROADMAP

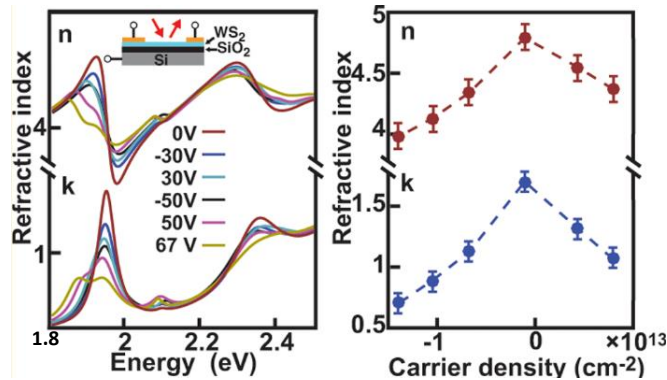


- Safe metal offset is required to prevent extra losses caused by metal contacts.
- Balanced EOT for tradeoff between efficiency and bandwidth.
- A narrower DLG width leads to enhanced performance in slot-based devices.

EXPLORATORY!

OTHER 2D-MATERIALS (MoS_2) FOR LOW
LOSS INTEGRATED PHOTONICS PHASE
SHIFTERS

MOTIVATION

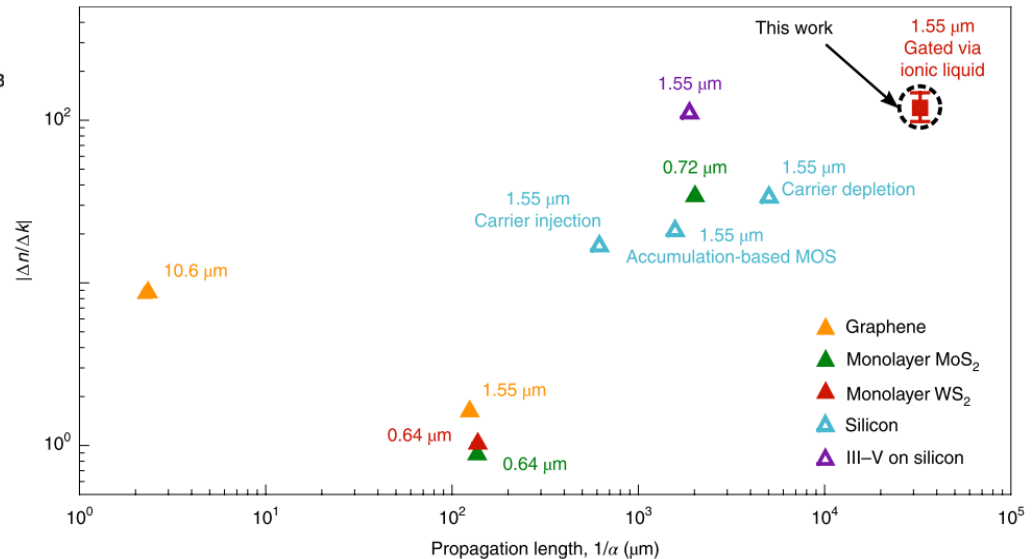


[1] Yu, Yiling, et al. "Giant gating tunability of optical refractive index in transition metal dichalcogenide monolayers." *Nano letters* 17.6 (2017): 3613-3618.

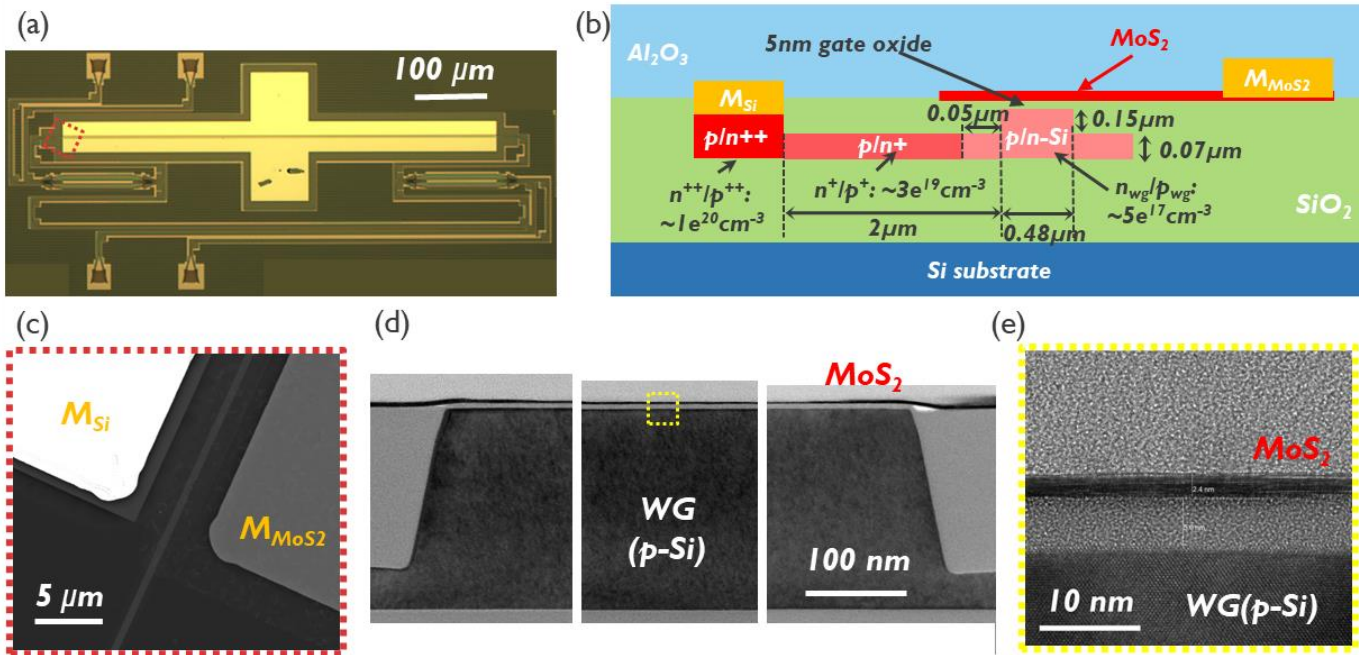
[2] Datta, Ipsita, et al. "Low-loss composite photonic platform based on 2D semiconductor monolayers." *Nature Photonics* 14.4 (2020): 256-262.

- TMDC (MX₂) exhibit strong index modulation at the excitonic peak.
- Also, it has strong index modulation within the C-band with low loss!

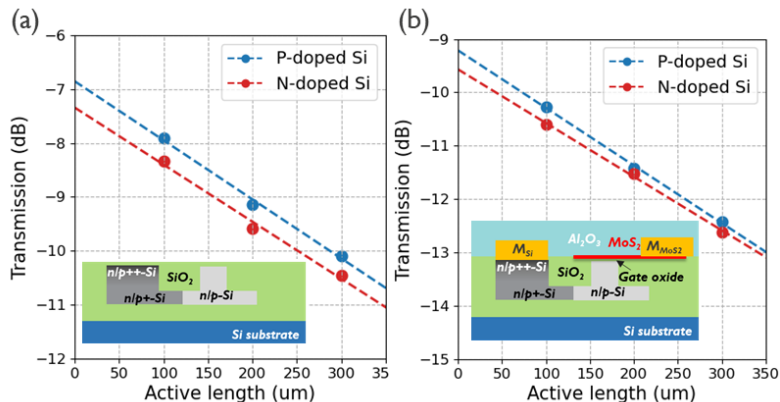
WS₂: $|\Delta n/\Delta k| \sim 125$



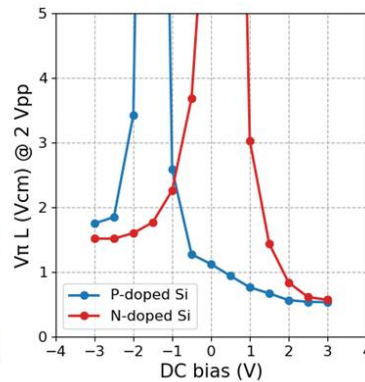
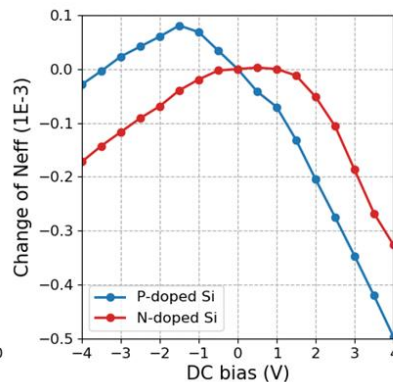
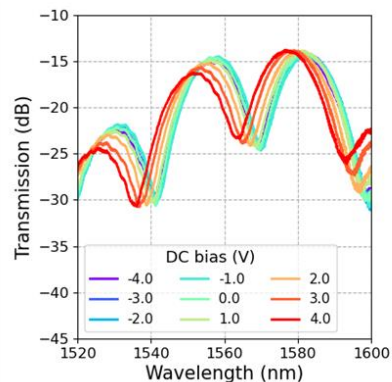
SINGLE-LAYER MoS₂ (SL-MoS₂)



SL-MoS2 EXPERIMENTAL PERFORMANCE



Propagation loss [dB/cm]	P-type	N-type
Before MoS ₂	109	106
After MoS ₂	108	100



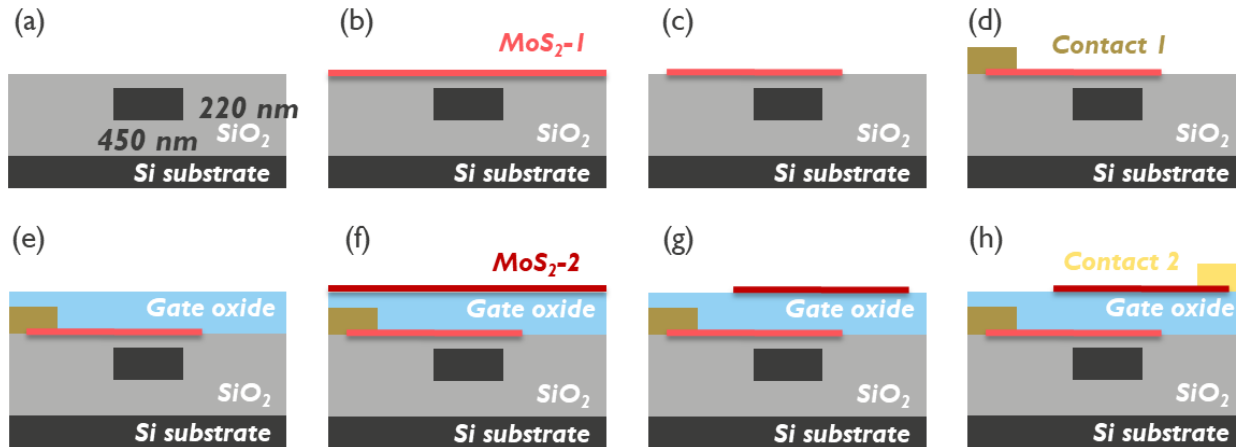
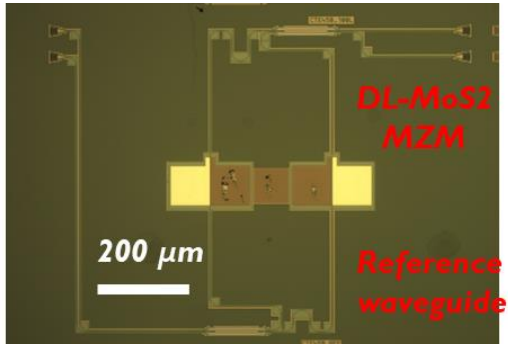
$$\Delta \phi = \frac{\text{wavelengthshift}}{FSR} 2\pi$$

$$V_{\pi} L = \frac{\Delta V}{\Delta \phi} \pi L ; \Delta V = V_{pp}$$

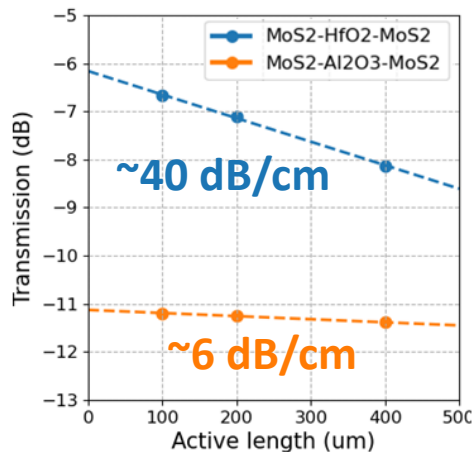
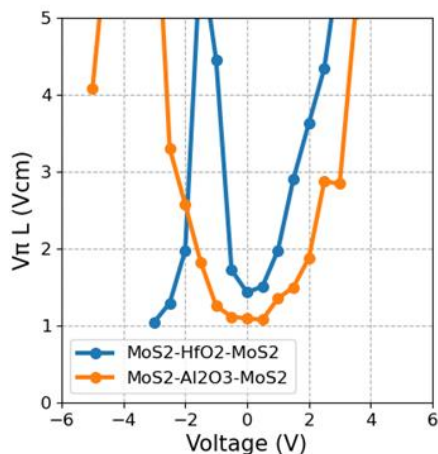
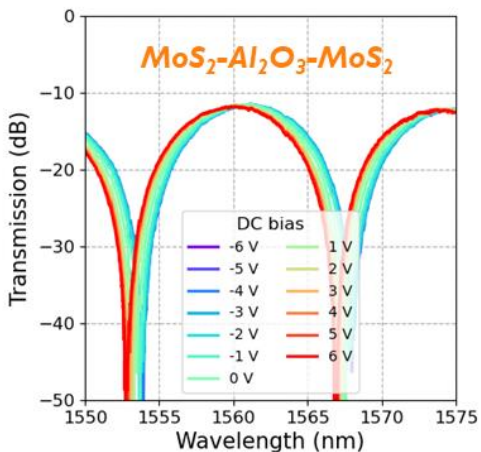
p-type: V_πL = 0.53 Vcm

n-type: V_πL = 0.57 Vcm

DUAL-LAYER MoS₂ (DL-MoS₂)



DL-MoS₂ EXPERIMENTAL PERFORMANCE



- DL-MoS₂ have lowest loss reported in this thesis.
 - 50 and 6.4 dB/cm for HfO₂ and Al₂O₃ device, respectively.
- FOM_{PM} outperform Si-based and 2D-materials based modulators.

BENCHMARKING TABLE

<i>MZMs</i>		<i>EOT</i>	<i>Loss</i>	$V_{\pi}L$	FOM_{pm}	<i>3dB bandwidth</i>
		<i>nm</i>	<i>dB/cm</i>	<i>Vcm</i>	<i>dBV</i>	<i>GHz</i>
<i>Si-oxide-Si</i>	[1]	5 & 10	60 & 54	0.25 & 0.4	15 & 22	5.6 & 11.2
<i>SLG</i>	[2]	10	~236	0.28	66.1	5
<i>DLG</i>	[3]	11	746	0.3	223	24
<i>WS₂-ITO</i>	[4]	-	135	0.8	108	0.33
<i>SL-MoS₂</i>	This Work	5	100	0.57	57	0.91
<i>DL-MoS₂</i>	This Work	9.5	6.4	0.97	6	0.3

[1] Abraham, A., et al. "Evaluation of the performances of a silicon optical modulator based on a silicon-oxide-silicon capacitor." 11th International Conference on Group IV Photonics (GFP). IEEE, 2014.

[2] Sorianello, V., et al. "Graphene–silicon phase modulators with gigahertz bandwidth." Nature Photonics 12.1 (2018): 40-44.

[3] Watson, Hannah. Graphene Modulators for Silicon Photonic Optical Links. Diss. University of Cambridge, 2021.

[4] Datta, Ipshita, et al. "Low-loss composite photonic platform based on 2D semiconductor monolayers." Nature Photonics 14.4 (2020): 256-262.

CONCLUSION

CONCLUSION

SCALABILITY

- The CMOS integration of graphene based photonics devices is established.
- The knowledge can be extended to other sophisticated building blocks.

PERFORMANCE

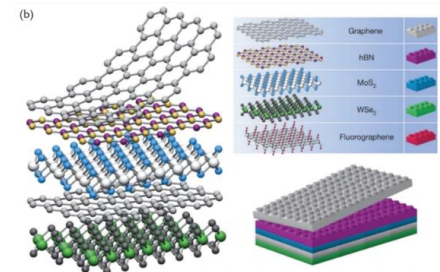
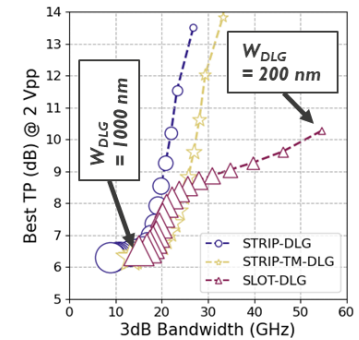
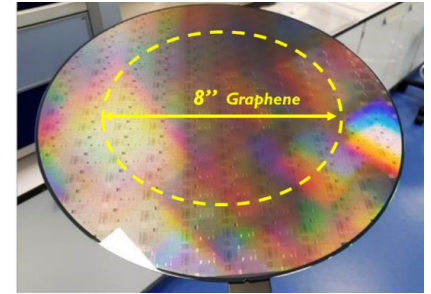
- The Figure of merits outperform state-of-the-art graphene-based modulators.
- Slot waveguide offers a new platform with greater design trade-off flexibility.

EXPLORATORY

- MoS₂ emerges as a promising material option for low-loss phase shifters.
- The exploration of other 2D materials remains an exciting subject for investigation .

Can 2D material based photonic devices be adopted in industry for the next generation of data communication and telecommunications applications?

YES! THEY CAN!



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Thank you all for the attention!

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